

Resource Summary Report

Generated by [NIF](#) on Sep 22, 2026

Oxford: PlasmaPro 100 ICPCVD Plasma Technolgy

RRID:SCR_020375

Type: Tool

Proper Citation

Oxford: PlasmaPro 100 ICPCVD Plasma Technolgy (RRID:SCR_020375)

Resource Information

URL: <https://plasma.oxinst.com/products/icpcvd/plasmapro-100-icpcvd>

Proper Citation: Oxford: PlasmaPro 100 ICPCVD Plasma Technolgy (RRID:SCR_020375)

Description: ICPCVD process module is designed to produce films at low growth temperatures, enabled through high density remote plasmas that achieves film quality with low substrate damage.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 100 ICPCVD Plasma Technolgy

Resource ID: SCR_020375

Alternate IDs: Model_Number_100_ICPCVD

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260919T195434+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 ICPCVD Plasma Technolgy.

No alerts have been found for Oxford: PlasmaPro 100 ICPCVD Plasma Technolgy.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.